

## CLAIMS

WHAT IS CLAIMED IS:

- 1           1.     A lithographic system for an integrated circuit fabrication  
2     process, the lithographic system comprising:  
3                 a computer; and  
4                 a configurable mask or reticle coupled to the computer,  
5     wherein the configurable mask or reticle allows light to be transmitted in a  
6     pattern controlled by a control signal from the computer.
- 1           2.     The lithographic system of claim 1, wherein the configurable  
2     mask or reticle is an LCD or LED matrix.
- 1           3.     The lithographic system of claim 1 further comprising:  
2                 a database for providing image information associated with a  
3     device to be patterned on a wafer, the computer using the image  
4     information to generate the control signal.
- 1           4.     The lithographic system of claim 3, wherein the database is  
2     stored on a storage media.
- 1           5.     The lithographic system of claim 3, wherein the image  
2     information is related to transistor structures.
- 1           6.     The lithographic system of claim 1, wherein the control  
2     signal is a video signal.
- 1           7.     A method of manufacturing an integrated circuit, the method  
2     comprising:

3                    providing a pattern of radiation via an LCD or LED assembly;  
4    and  
5                    performing a semiconductor fabrication process in  
6    accordance with the pattern of radiation.

1            8.     The method of claim 7, further comprising:  
2                    providing a second pattern of radiation via the LCD or LED  
3    assembly; and  
4                    performing a second semiconductor fabrication process in  
5    accordance with the second pattern of radiation.

1            9.     The method of claim 7, wherein the pattern is provided to a  
2    wafer in a step and repeat process.

1            10.    The method of claim 7, wherein the pattern is representative  
2    of a metal layer associated with the integrated circuit.

1            11.    The method of claim 7, wherein the pattern is representative  
2    of a structure associated with a transistor for the integrated circuit.

1            12.    The method of claim 7, wherein a representation of the  
2    pattern is stored electronically.

1            13.    The method of claim 7, wherein the integrated circuit is an  
2    ASIC.

1            14.    The method of claim 7, wherein the pattern is provided via  
2    the LCD assembly.

1            15.    A pattern generator for an integrated circuit fabrication  
2    system, the pattern generator comprising:

3 means for providing a pattern of light; and  
4 means for controlling the means for providing, wherein the  
5 means for controlling selects the pattern.

1 16. The pattern generator of claim 15, further comprising:  
2 means for providing a light through the means for providing a  
3 pattern.

1 17. The pattern generator of claim 16, further comprising:  
2 means for focusing the light on a wafer.

1 18. The pattern generator of claim 15, further comprising:  
2 means for storing elements, wherein the means for  
3 controlling creates a control signal representative of the pattern in  
4 response to the elements.

1 19. The pattern generator of claim 15, wherein the means for  
2 controlling includes a workstation executing a software program.

1 20. The pattern generator of claim 19, wherein the means for  
2 providing a pattern includes liquid crystals.

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